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Signature

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Neal R. Rueger	§	Group Art Unit: unk
	§	
	§	Examiner: unk
Assignee: Micron Technology, Inc.	§	
	§	Examiner phone: unk
Serial No.: unk	§	
	§	Atty. Dkt. No.: 102-0102US
Filed: herewith	§	
	§	
For: ***IMPROVED INDUCTIVELY COUPLED PLASMA CHAMBER ATTACHABLE TO A PROCESSING CHAMBER FOR ANALYSIS OF PROCESS GASES***	§	

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria VA, 22313-1450.

Sir:

In compliance with the duty of disclosure under 37 C.F.R. § 1.56, it is respectfully requested that this Information Disclosure Statement (IDS) be entered and the documents listed on attached Form PTO-1449 be considered by the Examiner and made of record. Copies of the listed documents are attached.

In accordance with 37 C.F.R §§ 1.97(g),(h), this IDS is not to be construed as a representation that a search has been made, and is not to be construed to be an admission that the

information cited is, or is considered to be, material to patentability as defined in 37 C.F.R. § 1.56(b), or that such information constitutes prior art.

This IDS is being filed prior to the receipt of a first Official Action reflecting an examination on the merits, and hence is believed to be timely filed in accordance with 37 C.F.R § 1.97(b). No fees are believed to be due in connection with the filing of this IDS. However, the Commissioner is authorized to deduct any necessary fees from Deposit Account No. 501922, referencing matter no. 102-0102US.

Applicant respectfully requests that the listed documents be considered and made of record in the present case, and that the Examiner initial the appropriate spaces on the Form 1449 to evidence the same

Respectfully submitted,

Terril G. Lewis, Reg. No. 46,065

March 31, 2004

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Form PTO-1449 (modified)	Atty. Docket No. 102-0102US	Serial No. unk
List of Patents and Publications for Applicant's INFORMATION DISCLOSURE STATEMENT	**Inventor/Applicant:** **Neal R. Rueger / Micron Technology, Inc.** **Title:** ***IMPROVED INDUCTIVELY COUPLED PLASMA CHAMBER ATTACHABLE TO A PROCESSING CHAMBER FOR ANALYSIS OF PROCESS GASES***	
(Use several sheets if necessary)	**Filing Date:** herewith	**Group:** unk

U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date of App.
	A1						

Foreign Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Country	Class	Sub Class	Translation Yes/No
	B1						

Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
	C1	Bladimiro Ruiz, Jr. & Herbert E. Litvak, "Investigation of Silicon Trench Etch Chemistry Using a Downstream Chemical Monitor," 4th AVS Int'l Conference on Microelectronics and Interfaces (2003)
	C2	Freddy Gaboriau et al., "Langmuir Probe Measurements in an Inductively Coupled Plasma: . . .," J. Vac. Sci. Technol., Vol. A20(3), pp. 919-27 (May/Jun 2002);
	C3	M.V. Malyshev et al., "Diagnostic Studies of Aluminum Etching in an Inductively Coupled Plasma System: . . .," J. Vac. Sci. Technol., Vol. A18(3), pp. 849-59 (May/Jun 2000)
	C4	D.M. Manos et al., "Characterization of Laboratory Plasmas With Probes," J. Vac. Sci. Technol., Vol. A3(3), pp. 1059-66 (May/Jun 1985)
	C5	S.M. Rossnagel et al., "Langmuir Probe Characterization of Magnetron Operation," J. Vac. Sci. Technol., Vol. A4(3), pp. 1822-25 (May/Jun 1986)
	C6	V. Kaeppelin et al., "Ion Energy Distribution Functions and Langmuir Probe Measurements in Low Pressure Argon Discharges," J. Vac. Sci. Technol., Vol. A20(2), pp. 526-29 (Mar/Apr 2002)
	C7	Terry A. Miller, "Optical Emission and Laser-Induced Fluorescence Diagnostics," J. Vac. Sci. Technol., Vol. A4(3), pp. 1768-72 (May/Jun 1986)

EXAMINER:	DATE CONSIDERED:

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Form PTO-1449 (modified)	Atty. Docket No. 102-0102US	Serial No. unk
List of Patents and Publications for Applicant's INFORMATION DISCLOSURE STATEMENT	**Inventor/Applicant:** **Neal R. Rueger / Micron Technology, Inc.** **Title:** ***IMPROVED INDUCTIVELY COUPLED PLASMA CHAMBER ATTACHABLE TO A PROCESSING CHAMBER FOR ANALYSIS OF PROCESS GASES***	
(Use several sheets if necessary)	**Filing Date:** herewith	**Group:** unk

Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
	C8	V.M. Donnelly, "A Simple Optical Emission Method for Measuring Percent Dissociations of Feed Gases in Plasmas: . . .," J. Vac. Sci. Technol., Vol. A14(3), pp. 1076-87 (May/Jun 1996)
	C9	A.D. Kuypers et al., "Emission Spectroscopy and Actinometry in a Magnetized Low Pressure Radio Frequency Discharge," J. Vac. Sci. Technol., Vol. A8(5), pp. 3736-45 (Sep/Oct 1990)
	C10	Zhimin Wan et al., "Electron Cyclotron Resonance Plasma Reactor for SiO_2 Etching: . . .," J. Vac. Sci. Technol., Vol. A13(4), pp. 2035-43 (Jul/Aug 1995)
	C11	

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